

The VDE/VDI-Society Microelectronics, Micro- and Precision Engineering (GMM) and UBC Microelectronics in cooperation with Altis, AMD-Saxony, AMTC, ASML, AVTF, BACUS, CEA/LETI, Crolles Alliance, Infineon/Quimonda, JEMI, KLA-Tencor, Minatec, MHS, Photonics, PMJ, SEMI-Europe, Sitelesc, SPIE, Toppan Photomasks, UMS and UBC Microelectronics are pleased to announce the

**23<sup>rd</sup> European Mask and Lithography  
Conference, EMLC2007  
at  
the Minatec Conference Center  
Grenoble, France  
January 22<sup>nd</sup> - January 25<sup>th</sup>, 2007**

**This is the first time the EMLC will be held in France.**

This three days conference is an internationally recognized meeting in its 23<sup>rd</sup> year. It has annually brought together scientists, researchers, engineers and developers to present papers at the forefront of photomask and lithography technologies.

The conference gives an overview of the present status and an outlook into the future of mask and lithography technologies and their associated technologies like resolution enhancement, data processing, resist, metrology, inspection, application, etc. It provides a place where mask makers, mask users, and their tool suppliers can find an opportunity to become acquainted with new developments and results. The conference also gives attendees the opportunity to meet with leading experts in fields of common interest.

The venue will take place on

**Monday, January 22<sup>nd</sup>, 2007 (welcome reception)**  
**Tuesday, January 23<sup>rd</sup>, 2007 (conference)**  
**Wednesday, January 24<sup>th</sup>, 2007 (conference)**  
**Thursday, January 25<sup>th</sup>, 2007 (conference)**

**at the Minatec Conference Center, Grenoble, France  
www.emlc2007.com**

**Technical Exhibition:** On Tuesday and Wednesday there will be a technical exhibition with booth space for about 30 exhibitors. Presentation tables and pin boards will be available. To be part of this Technical Exhibition please return the **attached registration form** to the conference chairperson as soon as possible as exhibition space is limited.

**Conference Chairperson and Exhibition Organization:**

Dr. Uwe Behringer, UBC Microelectronics,  
Auf den Beeten 5,

D-72119 Ammerbuch, Germany  
Phone: +49-171-455 3196, Fax: +49-7073-50216  
E-Mail: uwe.behringer.ubc@t-online.de

**Abstract Information:**

Please ensure that your abstract includes the following:

- Title of the presentation
- Name(s) of author(s) with affiliation and full address including e-mail. Please underline the presenting author's name.
- Biography of the presenting author
- Contact author with full address etc. If different from presenting author.

The quality of the abstracts will form the basis for selection of papers for the conference. The abstracts will be peer reviewed according to the following criteria:

- Originality of work
- Specific results that have been obtained
- Potential impact and interest to the attendees.

Therefore, we highly recommend that your abstract contains enough detail to clearly describe the content of the presentation. The abstracts should include at least one page of text (**minimum of 400 words**), the use of figures is encouraged. Commercial papers, or papers where significant information will be omitted, cannot be accepted.

**Abstract Submission by August 18<sup>th</sup>, 2006 to:**

**Dr. Uwe Behringer:** *uwe.behringer.ubc@t-online.de*  
**Mr. Jacques Waelpoel:** *jacques.waelpoel@asml.com*  
**Dr. Wilhelm Maurer:** *wilhelm.maurer@infineon.com*

Abstracts must be submitted in MS Word or PDF format.

All accepted abstracts will be printed, bound, and handed out to the participants of the conference.

**Notification to Authors**

Authors will be notified of the acceptance of their submissions by **October 13<sup>th</sup>**; further manuscript format and layout instructions will be provided at that time.

**Manuscripts for the Proceedings**

An original of the manuscript should be sent to the Conference Chairpersons, to both Program chairs (addresses shown above), **and** to the VDE/VDI-Society Microelectronics, Micro- and Precision Engineering (GMM) *gmm@vde.com* by **January 15<sup>th</sup>, 2006** at the latest.

The manuscripts are limited to **10 pages** (figures included).

All manuscripts will be subject to a critical peer review before they can be accepted for publication in the SPIE/VDE publication and in the SPIE Digital Library. **Please note: Late submissions may not be printed in the SPIE/VDE publication or be included in the SPIE Digital Library.**

**Conference Technical Topics:**

**Presentations are being solicited on the following topic areas:**

**Mask Manufacturing**

- Pattern Generation and Data Preparation
- Photomask Processes and Materials
- Mask Process Yield
- PS-Mask and Masks for OPC
- Mask for NGL: E-Beam, EUV, NIL,.....
- Metrology
- Defect Inspection and Repair
- Cleaning and Pelliclization

**Other Mask Topics**

- Mask Cost and Mask CoO
- Future Mask Demand
- Mask Business Considerations

**Lithography and Mask Applications**

- Resolution Enhancement Techniques
- MEEF
- Resist
- Mask Defect Printability
- Optical Materials
- Immersion Lithography
- Immersion Defectivity
- Alternate Immersion Fluids
- Emerging Lithography Technologies: 157nm, EUV, X-Ray, Nanoimprint and Embossing
- Double Exposure Lithography Strategies
- Maskless Lithography Techniques, ML2

**Mask and Lithography Equipment**

**Organizers:**

VDE/VDI-Society Microelectronics, Micro- and Precision Engineering (GMM), Dr.-Ing. Ronald Schnabel  
Stresemannallee 15, 60596 Frankfurt/Main, Germany,  
Phone: +49-69-6308-330, Fax: +49-69-63089828  
E-Mail: gmm@vde.com

In cooperation with:

UBC Microelectronics  
Dr. Uwe Behringer  
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72119 Ammerbuch, Germany  
Phone: +49-171 4553196, Fax: +49-7073-50216  
E-Mail: uwe.behringer.ubc@t-online.de

If you would like to receive the final program and an invitation to the

### 23<sup>rd</sup> Mask and Lithography Conference, EMLC2007

please e-mail or send us your e-mail address along with your full mailing address, or mail the information to the VDE/VDI Society Microelectronics, Micro- and Precision Engineering (GMM), Dr. Ronald Schnabel Stresemannallee 15, 60596 Frankfurt. FAX +49-69-6308 9828; E-Mail: gmm@vde.com

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Name

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Address

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e-mail Address

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Phone / Fax

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Please attach your business card here

**The EMLC 2007 program(\*) and the local committee are listed below.**

**Please find the total International Steering Committee of the EMLC on the website: [www.emlc2007.com](http://www.emlc2007.com)**

**Conference Chair:** Dr. U. Behringer, UBC Microelectronics, Ammerbuch, Germany

**Program Chair:** Mr. J. Waelpoel, ASML, Veldhoven, The Netherlands  
Dr. W. Maurer, Infineon, Munich, Germany

Dr. M. Arnz, Carl Zeiss SMT AG, Oberkochen, Germany(\*)  
Dr. U. Behringer, UBC Microelectronics, Ammerbuch Germany(\*)  
Dr. C. Blaesing, Vistec Semiconductor Systems, Wetzlar, Germany(\*)  
Mr. P. Chen, Taiwan Mask Corp., Hsinchu, Taiwan(\*)  
Prof. R. Engelstad, University of Wisconsin, Madison, WI, USA(\*)  
Mr. C. Gale, Applied Materials, Dresden, Germany(\*)  
Mr. B. Grenon, Grenon Consulting, Inc., Colchester, VT, USA(\*)  
Mr. N. Hayashi, Dai Nippon Printing Co. Ltd., Saitama, Japan(\*)  
Dr. A.C. Hourd, Compugraphics International Ltd., Glenrothes, Scotland  
Mr. R. Jonckheere, IMEC, Leuven, Belgium(\*)  
Dr. C.K. Kalus, SIGMA-C AG, Munich, Germany(\*)  
Mr. H. Lehon, KLA-Tencor Corporation, San Jose, CA, USA(\*)  
Dr. W. Maurer, Infineon, Munich, Germany(\*)  
Mr. B. Naber, Cadence Design Systems Inc., San Jose, CA, USA(\*)  
Dr. Ch. Pierrat, AMTC, Dresden, Germany(\*)  
Mr. E. Rausa, Unaxis USA Inc., Saint Petersburg, FL, USA(\*)  
Dr. C. Reita, CEA-LETI, Grenoble, France(\*)  
Dr. C. Romeo, ST-Microelectronics, Agrate Brianza, Italy(\*)  
Prof. H. Scheer, University of Wuppertal, Germany(\*)  
Dr. R. Schnabel, VDE/VDI-GMM, Frankfurt, Germany(\*)  
Mrs. I. Stolberg, Vistec Semiconductor Systems, Jena, Germany(\*)  
Dr. S. Tedesco, CEA-LETI, Grenoble, France(\*)  
Mr. M. Tissier, Toppan Photomasks S.A., Rousset Cedex, France(\*)  
Mr. J. Waelpoel, ASML, Veldhoven, NL(\*)  
Mr. J. Whittey, Vistec Semiconductor Systems, Oakdale, CA, USA(\*)  
Mr. H. Wolf, Photronics MZD GmbH, Dresden, Germany(\*)  
Mr. L. Zurbrick, KLA-Tencor Corporation, San Jose, CA, USA(\*)



**GMM** VDE/VDI-GESELLSCHAFT  
MIKROELEKTRONIK,  
MIKRO- UND FEINWERKTECHNIK



## CALL FOR PAPERS

### The 23<sup>rd</sup> European Mask and Lithography Conference EMLC 2007

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**VDE** 